

# Takaaki Aoki

## List of Publications by Year in Descending Order

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The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

156 papers	2,156 citations	25 h-index	40 g-index
174 ext. papers	2,266 ext. citations	2.2 avg, IF	4.46 L-index

#	Paper	IF	Citations
156	Innovative Technologies in Advanced SIMS Toward Organic and Biological Material Analysis. <i>Vacuum and Surface Science</i> , <b>2021</b> , 64, 458-465	0	
155	Secondary ion mass spectrometry measurements under ambient and humid conditions using MeV ions. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , <b>2020</b> , 38, 034014	1.3	2
154	Optimized Alkali-Metal Cationization in Secondary Ion Mass Spectrometry of Polyethylene Glycol Oligomers with up to / 10000: Dependence on Cation Species and Concentration. <i>Analytical Chemistry</i> , <b>2020</b> , 92, 1511-1517	7.8	0
153	MeV-SIMS measurement of lithium-containing electrolyte. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2020</b> , 479, 229-232	1.2	1
152	Recent Progress of SIMS Technique from Novel Primary Beams to Advanced Mass Spectrometers. <i>Vacuum and Surface Science</i> , <b>2018</b> , 61, 426-434	0	1
151	Cationization and fragmentation of molecular ions sputtered from polyethylene glycol under gas cluster bombardment: An analysis by MS and MS/MS. <i>International Journal of Mass Spectrometry</i> , <b>2018</b> , 430, 149-157	1.9	4
150	Fabrication of a Si lever structure made by double-angled etching with reactive gas cluster injection. <i>Applied Physics Letters</i> , <b>2017</b> , 110, 182105	3.4	0
149	Angled etching of Si by ClF <sub>3</sub> /Ar gas cluster injection. <i>Japanese Journal of Applied Physics</i> , <b>2017</b> , 56, 06HB024	0.2	4
148	Building and Development of Research Data Management Training Tool. <i>Journal of the Japan Society of Information and Knowledge</i> , <b>2017</b> , 27, 362-365	0.1	
147	Recent Developments of Cluster Ion Beam &mdash; From Nano-fabrication to Analysis of Bio-materials&mdash;. <i>Journal of the Vacuum Society of Japan</i> , <b>2016</b> , 59, 113-120		
146	Recent Progress in Cluster Beam Technique. <i>Journal of the Japan Society for Precision Engineering</i> , <b>2016</b> , 82, 309-314	0.1	0
145	Reactive etching by ClF <sub>3</sub> /Ar neutral cluster beam with scanning. <i>Japanese Journal of Applied Physics</i> , <b>2016</b> , 55, 06HB01	1.4	5
144	Secondary ion emission from leucine and isoleucine under argon gas-cluster ion bombardment. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , <b>2016</b> , 34, 03H102	1.3	3
143	Yields and images of secondary ions from organic materials by different primary Bi ions in time-of-flight secondary ion mass spectrometry. <i>Rapid Communications in Mass Spectrometry</i> , <b>2016</b> , 30, 476-82	2.2	6
142	Ambient analysis of liquid materials with Wet-SIMS. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2016</b> , 371, 189-193	1.2	6
141	Development of ambient SIMS using mega-electron-volt-energy ion probe. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , <b>2016</b> , 34, 03H111	1.3	8
140	Molecular dynamics simulations study of nano particle migration by cluster impact. <i>Surface and Coatings Technology</i> , <b>2016</b> , 306, 63-68	4.4	3

139	Development of Low-vacuum SIMS instruments with large cluster ion beam. <i>Surface and Interface Analysis</i> , <b>2016</b> , 48, 1119-1121	1.5	3
138	Molecular cluster emission in sputtering of amino acids by argon gas-cluster ions. <i>International Journal of Mass Spectrometry</i> , <b>2015</b> , 383-384, 31-37	1.9	4
137	Progress and applications of cluster ion beam technology. <i>Current Opinion in Solid State and Materials Science</i> , <b>2015</b> , 19, 12-18	12	38
136	Molecular dynamics simulations of cluster impacts on solid targets: implantation, surface modification, and sputtering. <i>Journal of Computational Electronics</i> , <b>2014</b> , 13, 108-121	1.8	21
135	Quantitative analysis of lipids with argon gas cluster ion beam secondary ion mass spectrometry. <i>Surface and Interface Analysis</i> , <b>2014</b> , 46, 1129-1132	1.5	
134	Analysis of liquid materials in low vacuum with Wet-SIMS. <i>Surface and Interface Analysis</i> , <b>2014</b> , 46, 1133-1136	1.36	8
133	Biomaterial imaging with MeV-energy heavy ion beams. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2014</b> , 332, 326-329	1.2	6
132	Prolific cluster emission in sputtering of phenylalanine by argon-cluster ion bombardment. <i>International Journal of Mass Spectrometry</i> , <b>2014</b> , 360, 54-57	1.9	7
131	Highly Accurate Lipid Analysis and Imaging Mass Spectrometry with Cluster SIMS. <i>Hyomen Kagaku</i> , <b>2014</b> , 35, 351-355		1
130	Lipid compounds analysis with MeV-SIMS apparatus for biological applications. <i>Surface and Interface Analysis</i> , <b>2014</b> , 46, 353-356	1.5	1
129	Low Vacuum SIMS Measurements of Higher Alcohols with MeV-energy Heavy Ion Beam. <i>Transactions of the Materials Research Society of Japan</i> , <b>2014</b> , 39, 265-268	0.2	2
128	Study on the detection limits of a new argon gas cluster ion beam secondary ion mass spectrometry apparatus using lipid compound samples. <i>Rapid Communications in Mass Spectrometry</i> , <b>2014</b> , 28, 917-20	2.2	12
127	Novel SIMS system with focused massive cluster ion source for mass imaging spectrometry with high lateral resolution. <i>Applied Physics Express</i> , <b>2014</b> , 7, 056602	2.4	32
126	Ion-induced damage evaluation with Ar cluster ion beams. <i>Surface and Interface Analysis</i> , <b>2013</b> , 45, 167-170	1.9	9
125	Development of gas cluster ion beam irradiation system with an orthogonal acceleration TOF instrument. <i>Surface and Interface Analysis</i> , <b>2013</b> , 45, 522-524	1.5	15
124	An electrostatic quadrupole doublet focusing system for MeV heavy ions in MeV-SIMS. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2013</b> , 315, 356-359	1.2	5
123	Molecular dynamics simulation study of damage formation and sputtering with huge fluorine cluster impact on silicon. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2013</b> , 303, 170-173	1.2	3
122	Ultrafine Particle Removal Using Gas Cluster Ion Beam Technology. <i>IEEE Transactions on Semiconductor Manufacturing</i> , <b>2013</b> , 26, 328-334	2.6	4

121	Peptide dissociation patterns in secondary ion mass spectrometry under large argon cluster ion bombardment. <i>Rapid Communications in Mass Spectrometry</i> , <b>2013</b> , 27, 1490-6	2.2	16
120	Molecular dynamics study of crater formation by core-shell structured cluster impact. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2012</b> , 282, 29-32	1.2	6
119	Depth profiling analysis of damaged arginine films with Ar cluster ion beams. <i>Surface and Interface Analysis</i> , <b>2012</b> , 44, 729-731	1.5	5
118	Energy effects on the sputtering yield of Si bombarded with gas cluster ion beams <b>2011</b> ,		6
117	Etching of metallic materials with Cl <sub>2</sub> gas cluster ion beam. <i>Surface and Coatings Technology</i> , <b>2011</b> , 206, 789-791	4.4	2
116	Highly sensitive molecular detection with swift heavy ions. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2011</b> , 269, 2251-2253	1.2	18
115	MeV-energy probe SIMS imaging of major components in washed and fractured animal cells. <i>Surface and Interface Analysis</i> , <b>2011</b> , 43, 363-366	1.5	4
114	Surface morphology of PMMA surfaces bombarded with size-selected gas cluster ion beams. <i>Surface and Interface Analysis</i> , <b>2011</b> , 43, 120-122	1.5	16
113	Using ellipsometry for the evaluation of surface damage and sputtering yield in organic films with irradiation of argon cluster ion beams. <i>Surface and Interface Analysis</i> , <b>2011</b> , 43, 84-87	1.5	7
112	Analysis of organic semiconductor multilayers with Ar cluster secondary ion mass spectrometry. <i>Surface and Interface Analysis</i> , <b>2011</b> , 43, 95-98	1.5	32
111	The effect of incident energy on molecular depth profiling of polymers with large Ar cluster ion beams. <i>Surface and Interface Analysis</i> , <b>2011</b> , 43, 221-224	1.5	19
110	Molecular dynamics simulations of large fluorine cluster impact on silicon with supersonic velocity. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2011</b> , 269, 1582-1585	1.2	7
109	Low-damage milling of an amino acid thin film with cluster ion beam. <i>Journal of Applied Physics</i> , <b>2011</b> , 110, 094701	2.5	2
108	Japan's Contributions to Ion Beam Technologies <b>2011</b> ,		1
107	Biomolecular Emission by Swift Heavy Ion Bombardment <b>2011</b> ,		1
106	Evaluation of surface damage on organic materials irradiated with Ar cluster ion beam <b>2011</b> ,		4
105	High Speed Si Etching with ClF <sub>3</sub> Cluster Injection <b>2011</b> ,		6
104	The effects of cluster size on sputtering and surface smoothing of PMMA with gas cluster ion beams. <i>Transactions of the Materials Research Society of Japan</i> , <b>2011</b> , 36, 309-312	0.2	1

103	Evaluation of damage depth on arginine films with molecular depth profiling by Ar cluster ion beam. <i>Transactions of the Materials Research Society of Japan</i> , <b>2011</b> , 36, 313-316	0.2	
102	Processing Techniques of Biomaterials Using Ar Cluster Ion Beam for Imaging Mass Spectrometry. <i>Transactions of the Materials Research Society of Japan</i> , <b>2010</b> , 35, 793-796	0.2	
101	MD simulation of small boron cluster implantation <b>2010</b> ,		1
100	Evaluation of Damage Layer in an Organic Film with Irradiation of Energetic Ion Beams. <i>Japanese Journal of Applied Physics</i> , <b>2010</b> , 49, 036503	1.4	12
99	Anisotropic Etching Using Reactive Cluster Beams. <i>Applied Physics Express</i> , <b>2010</b> , 3, 126501	2.4	10
98	MeV-energy probe SIMS imaging of major components in animal cells etched using large gas cluster ions. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2010</b> , 268, 1736-1740	1.2	17
97	Molecular dynamics simulations for gas cluster ion beam processes. <i>Vacuum</i> , <b>2010</b> , 84, 994-998	3.7	35
96	SIMS with highly excited primary beams for molecular depth profiling and imaging of organic and biological materials. <i>Surface and Interface Analysis</i> , <b>2010</b> , 42, 1612-1615	1.5	31
95	Recent Progress in Cluster Ion Beam Technology. <i>Hyomen Kagaku</i> , <b>2010</b> , 31, 564-571		3
94	SIMS Depth Profiling of Organic Materials with Ar Cluster Ion Beam. <i>Transactions of the Materials Research Society of Japan</i> , <b>2010</b> , 35, 785-788	0.2	
93	Sputtering Properties of Si by Size-Selected Ar Gas Cluster Ion Beam. <i>Transactions of the Materials Research Society of Japan</i> , <b>2010</b> , 35, 789-792	0.2	0
92	Sputtering yield measurements with size-selected gas cluster ion beams. <i>Materials Research Society Symposia Proceedings</i> , <b>2009</b> , 1181, 150		4
91	Matrix-free high-resolution imaging mass spectrometry with high-energy ion projectiles. <i>Journal of Mass Spectrometry</i> , <b>2009</b> , 44, 128-36	2.2	44
90	High-speed processing with Cl <sub>2</sub> cluster ion beam. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2009</b> , 267, 1444-1446	1.2	6
89	The emission process of secondary ions from solids bombarded with large gas cluster ions. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2009</b> , 267, 2601-2604	1.2	10
88	Precise and fast secondary ion mass spectrometry depth profiling of polymer materials with large Ar cluster ion beams. <i>Rapid Communications in Mass Spectrometry</i> , <b>2009</b> , 23, 1601-6	2.2	174
87	Molecular depth profiling of multilayer structures of organic semiconductor materials by secondary ion mass spectrometry with large argon cluster ion beams. <i>Rapid Communications in Mass Spectrometry</i> , <b>2009</b> , 23, 3264-8	2.2	86
86	Study of crater formation and sputtering process with large gas cluster impact by molecular dynamics simulations. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2009</b> , 267, 1424-1427	1.2	10

85	Imaging mass spectrometry with nuclear microprobes for biological applications. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2009</b> , 267, 2144-2148	1.2	12
84	Study of density effect of large gas cluster impact by molecular dynamics simulations. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2009</b> , 267, 2999-3001	1.2	11
83	Low Damage Etching of Polymer Materials for Depth Profile Analysis Using Large Ar Cluster Ion Beam. <i>Journal of Surface Analysis (Online)</i> , <b>2009</b> , 15, 275-278	0.1	2
82	A Processing Technique for Cell Surfaces Using Gas Cluster Ions for Imaging Mass Spectrometry. <i>Journal of the Mass Spectrometry Society of Japan</i> , <b>2009</b> , 57, 117-121	0.2	0
81	Carbon Nanotubes from a Divided Catalyst: the Carbon Transmission Method. <i>Applied Physics Express</i> , <b>2008</b> , 1, 034002	2.4	4
80	A fragment-free ionization technique for organic mass spectrometry with large Ar cluster ions. <i>Applied Surface Science</i> , <b>2008</b> , 255, 1588-1590	6.7	54
79	MD simulation study of the sputtering process by high-energy gas cluster impact. <i>Applied Surface Science</i> , <b>2008</b> , 255, 944-947	6.7	11
78	Secondary ion emission from Si bombarded with large Ar cluster ions under UHV conditions. <i>Applied Surface Science</i> , <b>2008</b> , 255, 880-882	6.7	7
77	High sputtering yields of organic compounds by large gas cluster ions. <i>Applied Surface Science</i> , <b>2008</b> , 255, 1148-1150	6.7	51
76	What size of cluster is most appropriate for SIMS?. <i>Applied Surface Science</i> , <b>2008</b> , 255, 1235-1238	6.7	41
75	Yield enhancement of molecular ions with MeV ion-induced electronic excitation. <i>Applied Surface Science</i> , <b>2008</b> , 255, 1591-1594	6.7	18
74	Recent Progress in Cluster Ion Beam. <i>Journal of Surface Analysis (Online)</i> , <b>2008</b> , 14, 196-203	0.1	5
73	Low Damage Etching and SIMS Depth Profiling with Large Ar Cluster Ions. <i>Transactions of the Materials Research Society of Japan</i> , <b>2008</b> , 33, 1043-1046	0.2	1
72	Imaging Mass Spectrometry with Swift Heavy Ions. <i>Journal of the Mass Spectrometry Society of Japan</i> , <b>2008</b> , 56, 201-208	0.2	1
71	High-Speed Nanoprocessing with Cluster Ion Beams. <i>Transactions of the Materials Research Society of Japan</i> , <b>2008</b> , 33, 1019-1022	0.2	
70	Low damage smoothing of magnetic materials using off-normal gas cluster ion beam irradiation. <i>Surface and Coatings Technology</i> , <b>2007</b> , 201, 8632-8636	4.4	6
69	Molecular dynamics study of monomer and dimer emission processes with high energy gas cluster ion impact. <i>Surface and Coatings Technology</i> , <b>2007</b> , 201, 8427-8430	4.4	5
68	Molecular dynamics study of surface modification with a glancing angle gas cluster ion beam. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2007</b> , 255, 265-268	1.2	12

67	Surface oxidation of Si assisted by irradiation with large gas cluster ion beam in an oxygen atmosphere. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2007</b> , 256, 350-353	1.2	5
66	Molecular dynamics simulations of surface smoothing and sputtering process with glancing-angle gas cluster ion beams. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2007</b> , 257, 645-648	1.2	14
65	Molecular dynamics study of glancing angle gas cluster irradiation on irregular-structured surfaces. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2007</b> , 261, 639-642	1.2	16
64	Measurements of secondary ions emitted from organic compounds bombarded with large gas cluster ions. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2007</b> , 256, 493-496	1.2	14 <sup>O</sup>
63	The effect of incident cluster ion energy and size on secondary ion yields emitted from Si. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2007</b> , 256, 528-531	1.2	25
62	Size effect in cluster collision on solid surfaces. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2007</b> , 257, 627-631	1.2	21
61	Cluster Ion Implantation - Prospects and Challenges- <b>2007</b> ,		1
60	Molecular dynamics simulations of surface modification and damage formation by gas cluster ion impacts. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2006</b> , 242, 517-519	1.2	27
59	High-intensity Si cluster ion emission from a silicon target bombarded with large Ar cluster ions. <i>Applied Surface Science</i> , <b>2006</b> , 252, 6550-6553	6.7	7
58	Secondary ion measurements for oxygen cluster ion SIMS. <i>Applied Surface Science</i> , <b>2006</b> , 252, 7290-7292	6.7	5
57	Molecular dynamics study of particle emission by reactive cluster ion impact. <i>Applied Surface Science</i> , <b>2006</b> , 252, 6466-6469	6.7	5
56	Molecular dynamics simulations of sequential cluster ion impacts. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2005</b> , 228, 46-50	1.2	20
55	Total sputtering yields of solids under MeV-energy Si ion bombardment. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2005</b> , 230, 483-488	1.2	2
54	Secondary neutral and ionized particle measurements under MeV-energy ion bombardment. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2005</b> , 230, 489-494	1.2	1
53	Molecular dynamics study of the angular dependence of reactive cluster impacts. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2005</b> , 241, 594-598	1.2	3
52	Size and energy distribution of gas cluster ion beam measured by energy resolved time of flight mass spectroscopy. <i>Surface and Coatings Technology</i> , <b>2005</b> , 196, 198-202	4.4	3
51	EXPRIMENTAL STUDY OF CLUSTER SIZE EFFECT WITH SIZE-SELECTED CLUSTER ION BEAM <b>2005</b> , 219-222		
50	Molecular Dynamics Simulations of the Cluster-size Effect on Sputtering Process with Reactive Gas Cluster Ions. <i>Materials Research Society Symposia Proceedings</i> , <b>2005</b> , 908, 1		



49 SURFACE STRUCTURE DEPENDENCE OF IMPACT PROCESSES OF GAS CLUSTER IONS **2005**, 231-234

48 GAS CLUSTER ION BEAM SOURCE FOR SECONDARY ION EMISSION MEASUREMENTS **2005**, 227-230

47 Low Damage Smoothing of Magnetic Materials using Oblique Irradiation of Gas Cluster Ion Beam. *Materials Research Society Symposia Proceedings*, **2004**, 843, 551 5

46 Molecular Dynamics Study of Surface Structure and Sputtering Process by Sequential Fluorine Cluster Impacts. *Materials Research Society Symposia Proceedings*, **2004**, 843, 571 4

45 Surface structure dependence of impact processes of gas cluster ions. *Nuclear Instruments & Methods in Physics Research B*, **2004**, 216, 185-190 1.2 16

44 A new secondary ion mass spectrometry (SIMS) system with high-intensity cluster ion source. *Nuclear Instruments & Methods in Physics Research B*, **2004**, 219-220, 463-467 1.2 55

43 Fast Neutral Ar Penetration during Gas Cluster Ion Beam Irradiation into Magnetic Thin Films. *Materials Research Society Symposia Proceedings*, **2003**, 792, 609

42 Molecular dynamics study of damage formation characteristics by large cluster ion impacts. *Nuclear Instruments & Methods in Physics Research B*, **2003**, 202, 278-282 1.2 49

41 Atomistic study of cluster collision on solid surfaces. *Nuclear Instruments & Methods in Physics Research B*, **2003**, 206, 838-841 1.2 8

40 Modeling of surface smoothing process by cluster ion beam irradiation. *Nuclear Instruments & Methods in Physics Research B*, **2003**, 206, 842-845 1.2 9

39 Defect characteristics by boron cluster ion implantation. *Nuclear Instruments & Methods in Physics Research B*, **2003**, 206, 855-860 1.2 13

38 Cluster species and cluster size dependence of damage formation by cluster ion impact. *Nuclear Instruments & Methods in Physics Research B*, **2003**, 206, 861-865 1.2 12

37 Molecular effect on projected range in ultralow-energy ion implantation. *Nuclear Instruments & Methods in Physics Research B*, **2003**, 211, 206-210 1.2 9

36 Secondary ion mass spectrometry with gas cluster ion beams. *Applied Surface Science*, **2003**, 203-204, 214-218 6.7 30

35 Molecular Dynamics Study Of Surface Morphological Evolution By Cluster Impacts. *Materials Research Society Symposia Proceedings*, **2003**, 792, 383

34 Experimental Study of Cluster Size Effect with Size-selected Cluster Ion Beam System. *Materials Research Society Symposia Proceedings*, **2003**, 792, 115 1

33 Secondary ion mass spectrometry with gas cluster ion beams. *Nuclear Instruments & Methods in Physics Research B*, **2002**, 190, 860-864 1.2 37

32 Threshold Energy for Generating Damage with Cluster Ion Irradiation. *Materials Research Society Symposia Proceedings*, **2002**, 749, 1



31	Study of Surface Morphological Evolution by Cluster Ion Irradiation on Solid Targets. <i>Materials Research Society Symposia Proceedings</i> , <b>2002</b> , 749, 1		
30	Cluster size effect on reactive sputtering by fluorine cluster impact using molecular dynamics simulation. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2001</b> , 180, 164-170	1.2	9
29	Molecular dynamics and Monte-Carlo simulation of sputtering and mixing by ion irradiation. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2001</b> , 180, 312-316	1.2	24
28	Molecular dynamics simulation of fluorine ion etching of silicon. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2001</b> , 180, 317-321	1.2	10
27	Characterization of Damage Induced by Cluster Ion Implantation. <i>Materials Research Society Symposia Proceedings</i> , <b>2001</b> , 669, 1		3
26	Photoluminescence study of defects induced by B10H14 ions. <i>Materials Research Society Symposia Proceedings</i> , <b>2001</b> , 669, 1		
25	Secondary Ion Mass Spectrometry with Gas Cluster Ion Beams. <i>Materials Research Society Symposia Proceedings</i> , <b>2000</b> , 647, 1		
24	Ar Cluster Ion Bombardment Effects on Semiconductor Surfaces. <i>Materials Research Society Symposia Proceedings</i> , <b>2000</b> , 647, 1		1
23	Molecular Dynamics Simulations of Cluster Ion Impact on Diamond Surface. <i>Materials Research Society Symposia Proceedings</i> , <b>2000</b> , 650, 3401		5
22	STM observation of surface vacancies created by ion impact. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2000</b> , 164-165, 650-655	1.2	14
21	Molecular dynamics simulation of fluorine cluster ion impact. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2000</b> , 164-165, 546-552	1.2	5
20	Nano-processing with gas cluster ion beams. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>2000</b> , 164-165, 944-959	1.2	73
19	Cluster size dependence of the impact process on a carbon substrate. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>1999</b> , 153, 264-269	1.2	35
18	Cluster ion bombardment on atomically flat Au(111) solid surfaces. <i>Materials Chemistry and Physics</i> , <b>1998</b> , 54, 76-79	4.4	30
17	Molecular dynamics simulation of a carbon cluster ion impacting on a carbon surface. <i>Materials Chemistry and Physics</i> , <b>1998</b> , 54, 139-142	4.4	21
16	Energy dependence of a single trace created by C60 ion impact. <i>Materials Chemistry and Physics</i> , <b>1998</b> , 54, 143-146	4.4	25
15	Low-temperature formation of perovskite PbTiO <sub>3</sub> films by O <sub>2</sub> cluster ion-assisted deposition. <i>Materials Chemistry and Physics</i> , <b>1998</b> , 54, 255-257	4.4	6
14	Angular distributions of the particles sputtered with Ar cluster ions. <i>Materials Chemistry and Physics</i> , <b>1998</b> , 54, 262-265	4.4	42

13	Reduction of boron transient enhanced diffusion in silicon by low-energy cluster ion implantation. <i>Materials Chemistry and Physics</i> , <b>1998</b> , 54, 80-83	4.4	33
12	Non-linear processes in the gas cluster ion beam modification of solid surfaces. <i>Materials Science &amp; Engineering A: Structural Materials: Properties, Microstructure and Processing</i> , <b>1998</b> , 253, 249-257	5.3	59
11	Computer Simulation of Annealing after Cluster Ion Implantation. <i>Materials Research Society Symposia Proceedings</i> , <b>1998</b> , 532, 147		
10	Ultra Shallow Junction Formation by Cluster Ion Implantation. <i>Materials Research Society Symposia Proceedings</i> , <b>1998</b> , 532, 17		7
9	Vacuum Nanotechnology. Synthesis of New Materials and Characterization of Surfaces and Interfaces. Cluster Ion Implantation and Device Processes.. <i>Shinku/Journal of the Vacuum Society of Japan</i> , <b>1998</b> , 41, 932-939		
8	Molecular Dynamics Simulation of Fullerene Cluster Ion Impact. <i>Materials Research Society Symposia Proceedings</i> , <b>1997</b> , 504, 81		2
7	Size Dependence of Bombardment Characteristics Produced by Cluster Ion Beams. <i>Materials Research Society Symposia Proceedings</i> , <b>1997</b> , 504, 93		4
6	Gas cluster ion beam processing <b>1997</b> ,		2
5	Non-linear effects in high energy cluster ion implantation <b>1997</b> ,		4
4	STM observation of HOPG surfaces irradiated with Ar cluster ions. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>1997</b> , 121, 498-502	1.2	58
3	Molecular dynamics simulation of damage formation by cluster ion impact. <i>Nuclear Instruments &amp; Methods in Physics Research B</i> , <b>1997</b> , 121, 49-52	1.2	73
2	A New Sputter Etching Technology by Gas-Cluster Ion Beam.. <i>Hyomen Kagaku</i> , <b>1997</b> , 18, 743-751		
1	Range and Damage Distribution in Cluster Ion Implantation. <i>Materials Research Society Symposia Proceedings</i> , <b>1996</b> , 438, 363		12